

SEMICONDUCTOR CONDUCTIVE PATTERN
FORMATION METHOD

ABSTRACT OF THE INVENTION

5 A method for forming a conductive or magnetic
pattern for a semiconductor or other electronic device
includes patterning a mask layer outwardly from a
conductive layer of the semiconductor device. The
patterning defines portions of the conductive layer where
vias through the conductive layer are desired. The
method also includes exposing the semiconductor device to
a plasma. The plasma converts the unmasked portions of
10 the conductive layer into a compound. The method further
includes exposing the semiconductor device to a treatment
process to selectively remove the compound. The mask
layer may be removed either before or after removal of
the compound, thereby providing the unmasked conductive
15 layer in the desired pattern.